Amendments to the Claims:

1. (Currently amended) A support fixture for holding at least one wafer comprising:

a boat comprised of a material selected from the group consisting of silicon carbide and graphite;

a first layer on at least a portion of said boat and comprised of silicon carbide; ~~and~~

a second layer on at least a portion of said first layer and comprised of polysilicon; and

at least one wafer held by a portion of said boat coated with both said first and second layers, said at least one wafer in contact with said second layer.

2. (Original) A support fixture according to Claim 1 wherein said first layer has a greater purity than said boat.

3. (Original) A support fixture according to Claim 1 wherein said second layer has a hardness that more closely matches a hardness of the at least one wafer than a hardness of said boat.

4. (Original) A support fixture according to Claim 1 wherein said second layer has a coefficient of thermal expansion that more closely matches a coefficient of thermal expansion of the at least one wafer than a coefficient of thermal expansion of said boat.

5. (Original) A support fixture according to Claim 1 wherein said first layer completely surrounds said boat.

6. (Original) A support fixture according to Claim 1 wherein said first and second layers are chemical vapor deposition layers.

7. (Currently amended) A support fixture for holding at least one wafer comprising:

a boat;

a first layer on at least a portion of said boat, wherein said first layer has a greater purity than said boat; ~~and~~

a second layer on at least a portion of said first layer, wherein said second layer is formed of a different material than said first layer and said boat, and wherein said second layer has at least one material property selected from the group consisting of: (i) a hardness that more closely matches a hardness of the at least one wafer than a hardness of said boat, and (ii) a coefficient of thermal expansion that more closely matches a coefficient of thermal expansion of the at least one wafer than a coefficient of thermal expansion of said boat; and

at least one wafer held by a portion of said boat coated with both said first and second layers, said at least one wafer in contact with said second layer.

8. (Original) A support fixture according to Claim 7 wherein said first layer and said boat are comprised of silicon carbide.

9. (Original) A support fixture according to Claim 7 wherein said second layer is comprised of polysilicon.

10. (Original) A support fixture according to Claim 7 wherein said first layer completely surrounds said boat.

11. (Original) A support fixture according to Claim 7 wherein said first and second layers are chemical vapor deposition layers.

12. (Withdrawn) A method of fabricating a support fixture for holding at least one wafer comprising:

providing a boat comprised of a material selected from the group consisting of silicon carbide and graphite;

depositing a first layer of silicon carbide on at least a portion of said boat; and

depositing a second layer of polysilicon on at least a portion of the first layer.

13. (Withdrawn) A method according to Claim 12 wherein depositing the first layer comprises depositing the first layer so as to completely surround the boat.

14. (Withdrawn) A method according to Claim 12 wherein depositing the first layer comprises depositing the first layer via chemical vapor deposition.

15. (Withdrawn) A method according to Claim 12 wherein depositing the second layer comprises depositing the second layer via chemical vapor deposition.

16. (Withdrawn) A method of fabricating a support fixture for holding at least one wafer comprising:

depositing a first layer on at least a portion of a boat, wherein depositing the first layer comprises depositing a first layer that has a greater purity than the boat; and

depositing a second layer on at least a portion of the first layer, wherein depositing the second layer comprises depositing a second layer that is formed of a different material than the first layer and the boat and that has at least one material property selected from the group consisting of: (i) a hardness that more closely matches a hardness of the at least one wafer than a hardness of the boat, and (ii) a coefficient of thermal expansion that more closely matches a coefficient of thermal expansion of the at least one wafer than a coefficient of thermal expansion of the boat.

17. (Withdrawn) A method according to Claim 16 wherein the boat is comprised of silicon carbide, and wherein depositing the first layer comprises depositing a first layer comprised of silicon carbide.

18. (Withdrawn) A method according to Claim 16 wherein depositing the second layer comprises depositing a second layer comprised of polysilicon.

19. (Withdrawn) A method according to Claim 16 wherein depositing the first layer comprises depositing the first layer so as to completely surround the boat.

20. (Withdrawn) A method according to Claim 16 wherein depositing the first layer comprises depositing the first layer via chemical vapor deposition.

21. (Withdrawn) A method according to Claim 16 wherein depositing the second layer comprises depositing the second layer via chemical vapor deposition.